

EE-612:

Lecture 13

Threshold Voltage and MOSFET Capacitances

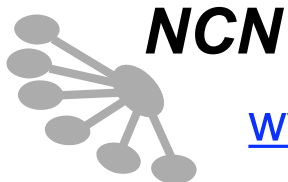
Mark Lundstrom

Electrical and Computer Engineering

Purdue University

West Lafayette, IN USA

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outline

- 1) Threshold Voltage
- 2) Body Effect
- 3) MOSFET Capacitances

threshold voltage

$$V_T = V_{FB} + 2\psi_B - Q_D(2\psi_B)/C_{OX}$$

$$V_T = V_{FB} + 2\psi_B + \sqrt{2q\epsilon_{Si}N_A(2\psi_B)}/C_{OX}$$

70 nm technology node (ITRS 2005 Ed.)

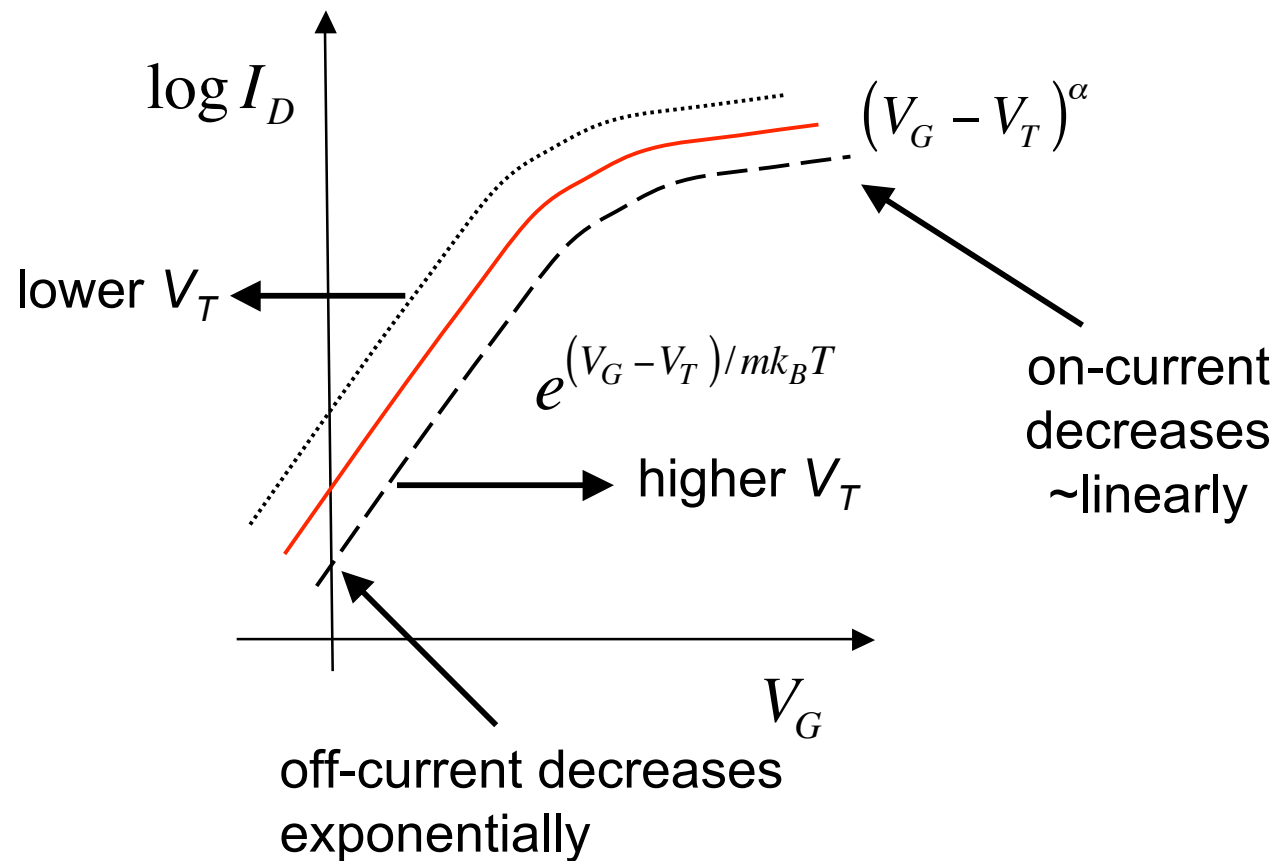
$$N_A \approx 4.6 \times 10^{18} \text{ cm}^{-3} \quad EOT \approx 1.1 \text{ nm}$$

$$\psi_B \approx 0.52 \text{ V}$$

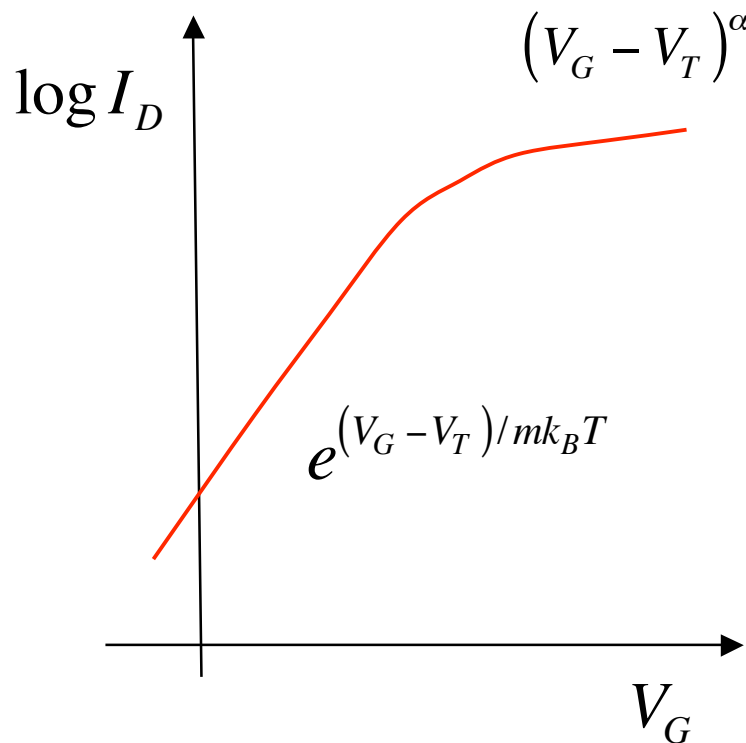
$$V_{FB} = \phi_{ms} \approx -0.55 - \psi_B \approx -1.07 \text{ V}$$

$$V_T \approx 0.38 \text{ V}$$

required V_T



required V_T



V_T selection is a trade-off between high on-current (low V_T) and low off-current (high V_T).

High-performance (high I_{ON}):

$$V_{DD} = 1.1V$$

$$V_T = 0.17V \quad (15\% \text{ of } V_{DD})$$

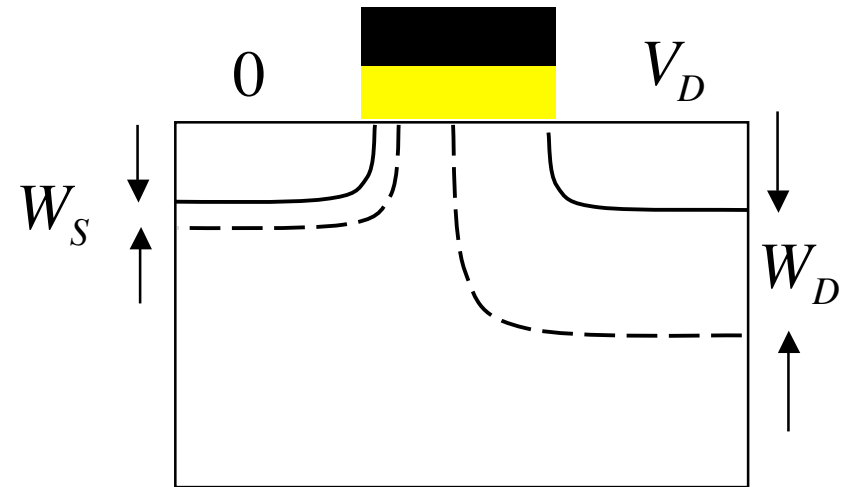
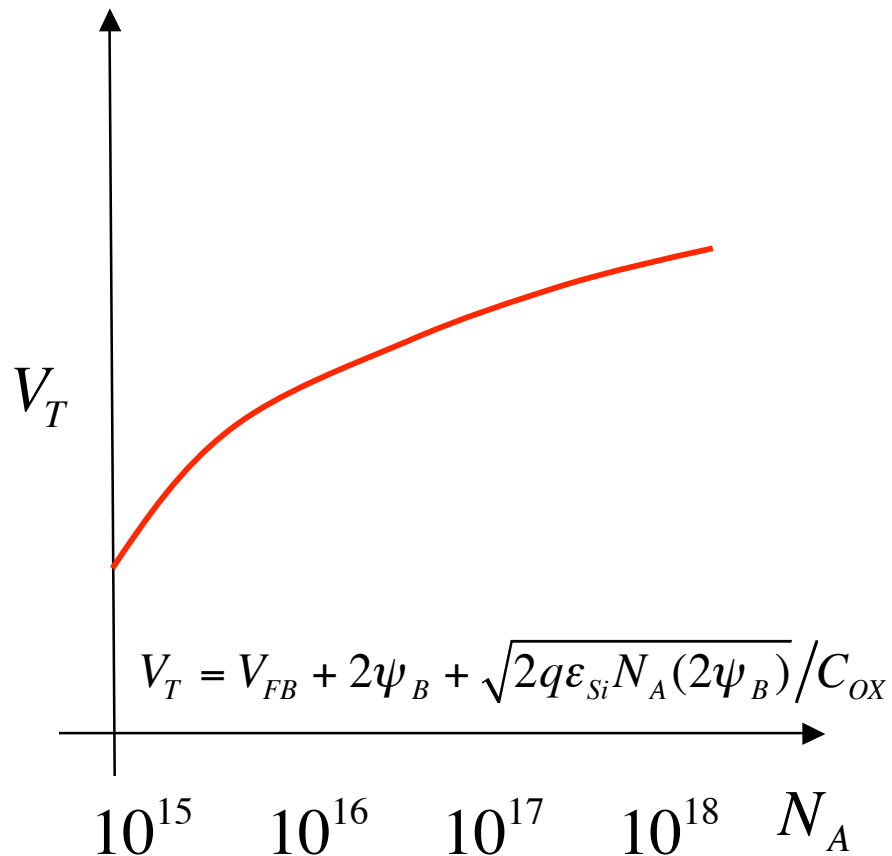
Low-power (low I_{OFF}):

$$V_{DD} = 1.2V$$

$$V_T = 0.52V \quad (43\% \text{ of } V_{DD})$$

60 nm node from ITRS 2005 Ed.

V_T engineering



N_A (min) : punch through
 $W_S + W_D < L$

N_A (max) : tunneling
 (also C_J and body effect)

V_T temperature dependence

$$V_T = V_{FB} + 2\psi_B + \sqrt{2q\epsilon_{Si}N_A(2\psi_B)/C_{OX}}$$

$$V_T = -\frac{E_G}{2q} + \psi_B + \sqrt{4q\epsilon_{Si}N_A\psi_B/C_{OX}}$$

$$\frac{dV_T}{dT} = -\frac{1}{2q} \frac{dE_G}{dT} + \left(1 + \sqrt{2\epsilon_{Si}qN_A/\psi_B/C_{OX}}\right) \frac{d\psi_B}{dT}$$

$$\frac{dV_T}{dT} = -\frac{1}{2q} \frac{dE_G}{dT} + \left(1 + 2C_{DM}/C_{OX}\right) \frac{d\psi_B}{dT}$$

$$m = 1 + C_{DM}/C_{OX}$$

V_T temperature dependence (ii)

$$\frac{dV_T}{dT} = -\frac{1}{2q} \frac{dE_G}{dT} + (2m-1) \frac{d\psi_B}{dT}$$

$$\psi_B = \frac{k_B T}{q} \ln(N_A/n_i) \quad n_i = \sqrt{N_C N_V} e^{-E_G/2k_B T}$$

$$\frac{dV_T}{dT} = -(2m-1) \frac{k_B}{q} \left[\ln\left(\frac{\sqrt{N_C N_V}}{N_A}\right) + \frac{3}{2} \right] + \frac{(m-1)}{q} \frac{dE_G}{dT}$$

eqn. (3.45) of Taur and Ning

V_T temperature dependence (iii)

$$\left. \begin{array}{l} N_A \approx 10^{16} \text{ cm}^{-3} \\ m \approx 1.1 \end{array} \right\} \frac{dV_T}{dT} \approx -1 \text{ mV/K}$$

$$\left. \begin{array}{l} N_A \approx 10^{18} \text{ cm}^{-3} \\ m \approx 1.3 \end{array} \right\} \frac{dV_T}{dT} \approx -0.7 \text{ mV/K}$$

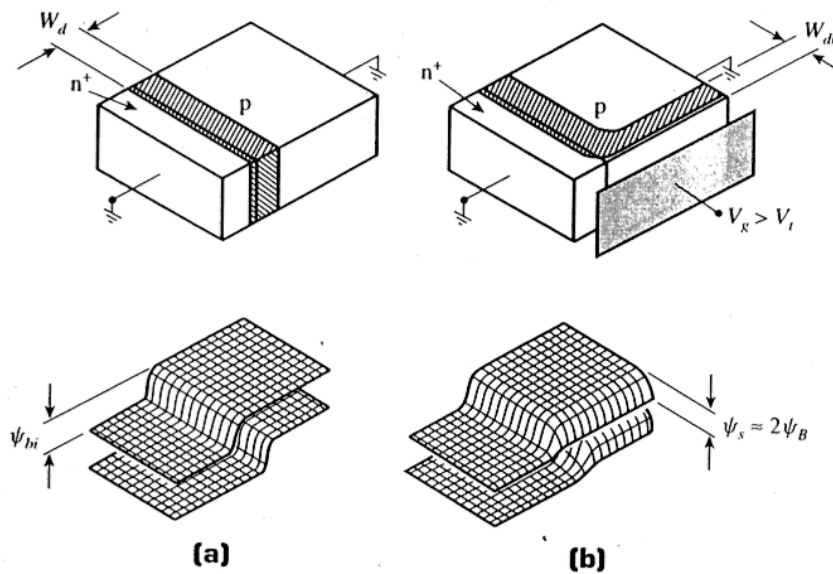
$$V_T(100^\circ\text{C}) \approx V_T(25^\circ\text{C}) - (55 - 75 \text{ mV})$$

$$I_{OFF}(100^\circ\text{C}) \approx 30 - 50 \times I_{OFF}(25^\circ\text{C})$$

outline

- 1) Threshold Voltage
- 2) Body Effect**
- 3) MOSFET Capacitances

recall



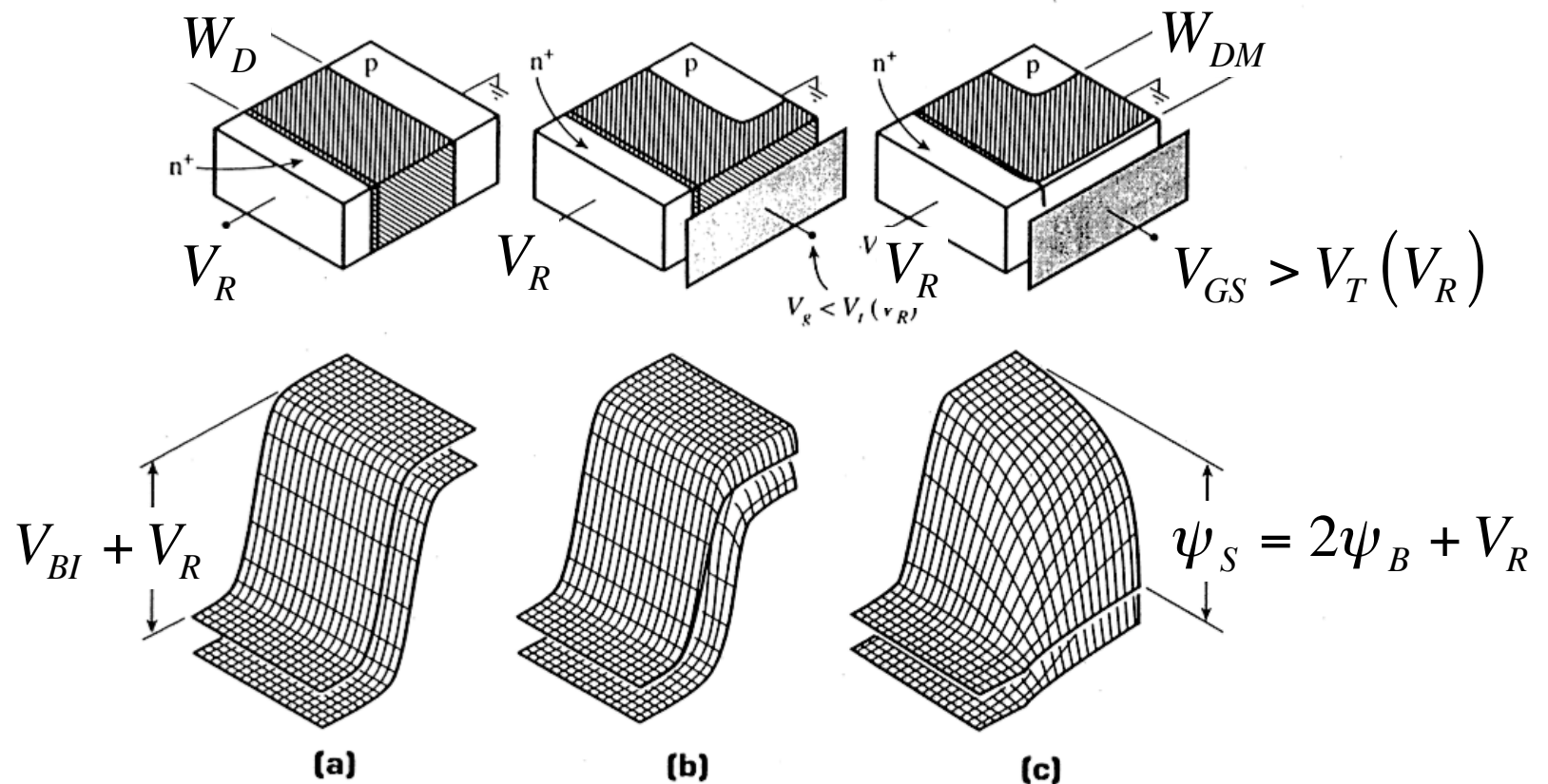
Gated doped or p-MOS with adjacent n^+ region

a) gate biased at flat-band

b) gate biased in inversion

A. Grove, *Physics of Semiconductor Devices*, 1967.

recall



Gated doped or p-MOS with adjacent, reverse-biased n⁺ region

a) gate biased at flat-band

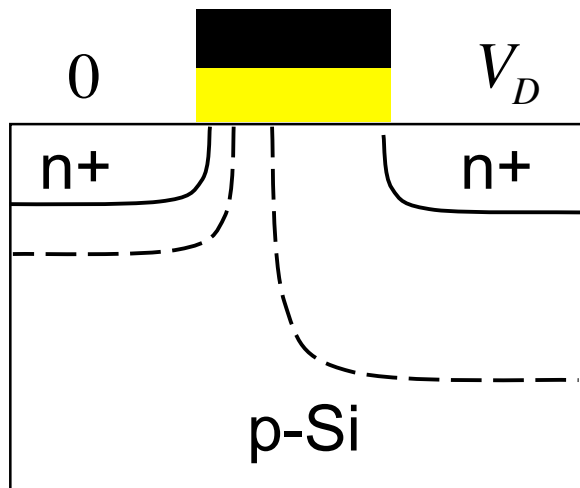
b) gate biased in depletion

b) gate biased in inversion

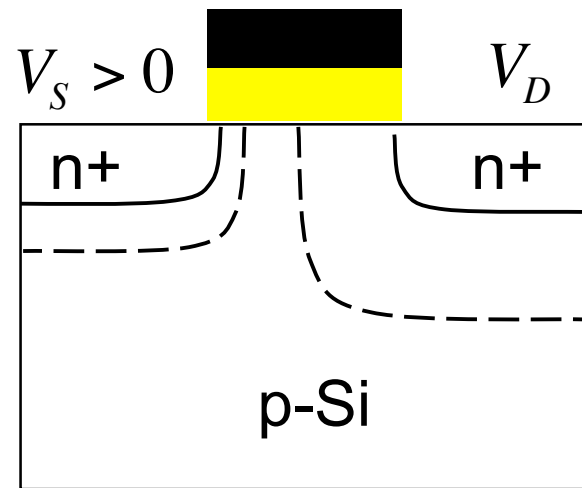
A. Grove, *Physics of Semiconductor Devices*, 1967.

backgate voltage

$$V_T = V_{FB} + 2\psi_B + \sqrt{2q\epsilon_{Si}N_A(2\psi_B + V_{SB})}/C_{OX}$$



$$V < 0 \ (V_{SB} > 0)$$



$$V = 0 \ (V_{SB} > 0)$$

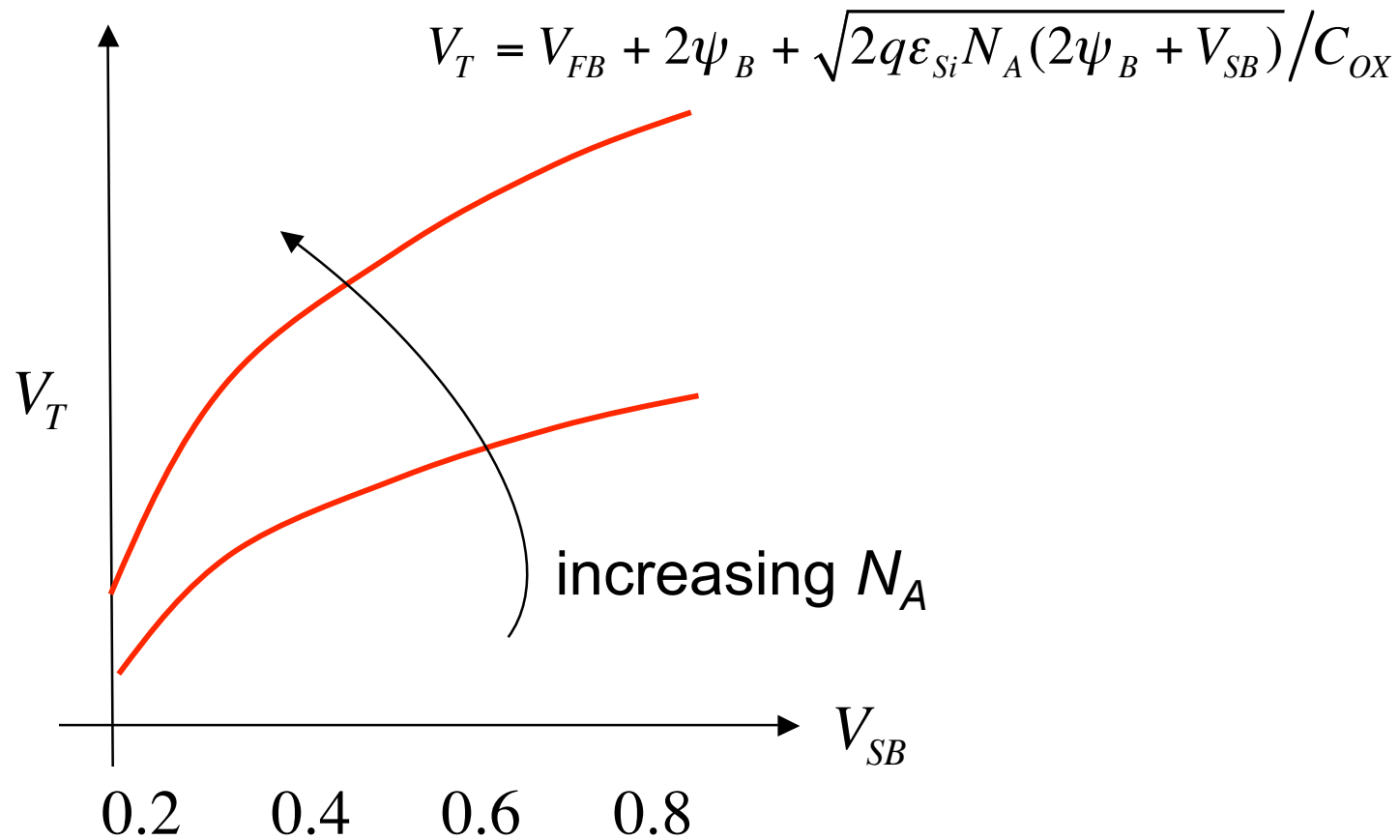
body effect

$$V_T = V_{FB} + 2\psi_B + \sqrt{2q\epsilon_{Si}N_A(2\psi_B + V_{SB})}/C_{OX}$$

$$V_T = V_{FB} + 2\psi_B + \gamma \sqrt{2\psi_B + V_{SB}}/C_{OX}$$

$$\gamma = \sqrt{2q\epsilon_{Si}N_A} \quad \text{body effect coefficient}$$

V_T vs. backgate voltage



substrate sensitivity

$$V_T = V_{FB} + 2\psi_B + \sqrt{2q\epsilon_{Si}N_A(2\psi_B + V_{SB})}/C_{OX}$$

$$\frac{dV_T}{dV_{SB}} = \frac{\sqrt{q\epsilon_{Si}N_A / 2(2\psi_B + V_{SB})}}{C_{OX}}$$

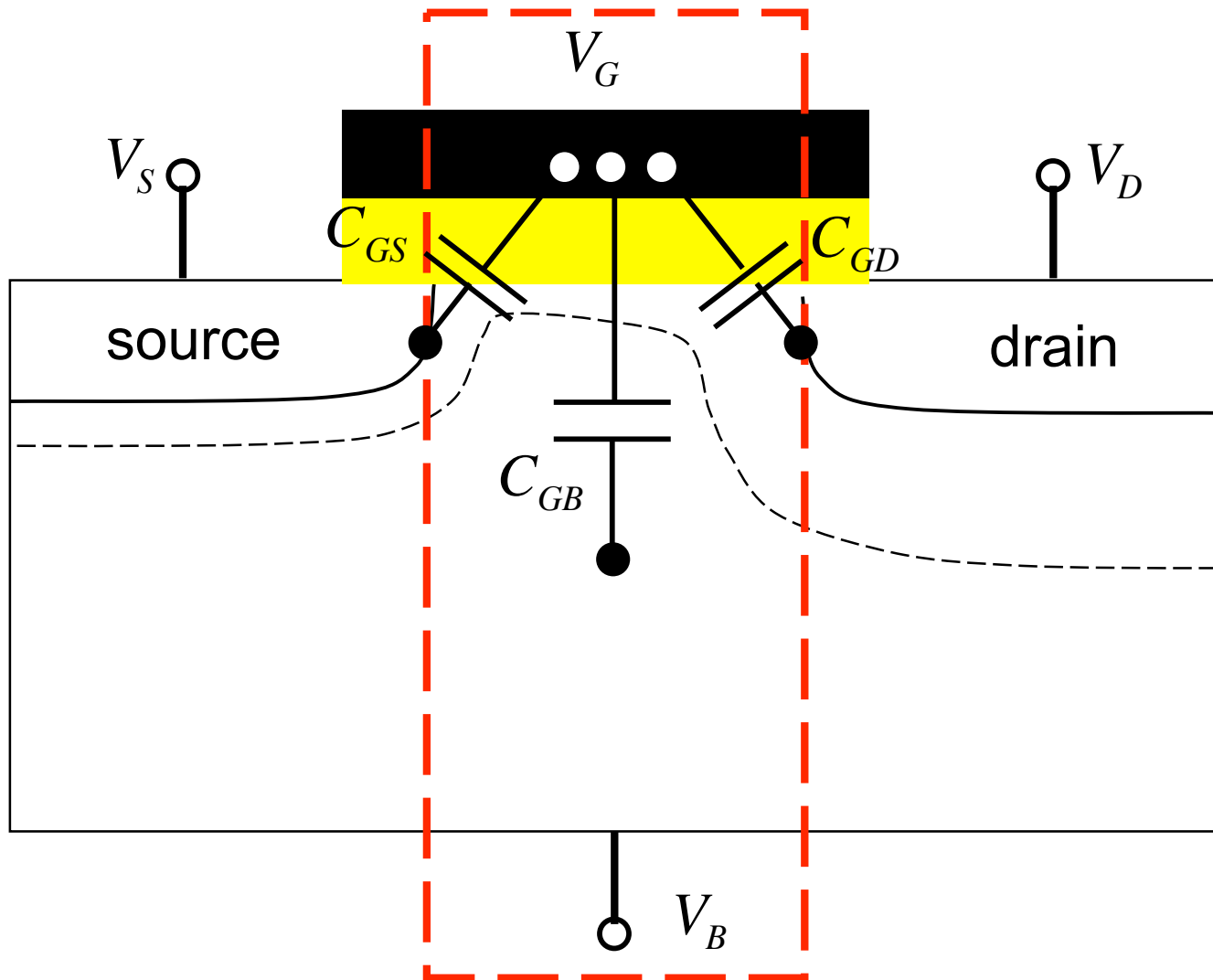
$$\left. \frac{dV_T}{dV_{SB}} \right|_{V_{SB}=0} = \frac{C_{DM}}{C_{OX}} = m - 1$$

body effect coefficient

outline

- 1) Threshold Voltage
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- 3) **MOSFET Capacitances**

intrinsic MOSFET C's



below threshold

$$\bar{Q}_G = W \int_0^L Q_G(y) dy \quad \text{F}$$

$$\bar{Q}_G \approx -WLQ_D$$

$$C_{GS} = \frac{\partial \bar{Q}_G}{\partial V_{GS}} \approx 0$$

$$C_{GD} = \frac{\partial \bar{Q}_G}{\partial V_{GD}} \approx 0$$

$$C_{GB} = \frac{\partial \bar{Q}_G}{\partial V_{GB}} = WL \left(\frac{1}{C_{OX}} + \frac{1}{C_D} \right)^{-1}$$

above threshold

$$\bar{Q}_G \approx -W \int_0^L C_G [V_G - V_T - V(y)] dy \quad \text{F}$$

$$I_D = -WC_G (V_G - V_T - V) \mu_{eff} \frac{dV}{dy}$$

$$I_D = \frac{W}{L} \mu_{eff} C_G (V_{GS} - V_T - 0.5V_{DS}) V_{DS} \quad V_{GD} = V_{GS} - V_{DS}$$

$$I_D = \frac{W}{2L} \mu_{eff} C_G \left[(V_{GS} - V_T)^2 - (V_{GD} - V_T)^2 \right] \quad (1)$$

above threshold

$$\bar{Q}_G \approx -W \int_0^L C_G [V_G - V_T - V(y)] dy \quad \text{F}$$

$$I_D = -WC_G (V_G - V_T - V) \mu_{eff} \frac{dV}{dy}$$

$$dy = -WC_G (V_G - V_T - V) \mu_{eff} dV / I_D$$

$$\bar{Q}_G \approx \frac{\mu_{eff} W^2 C_G^2}{I_D} \int_0^{V_{DS}} [V_G - V_T - V]^2 dV \quad (2)$$

above threshold

$$I_D = \frac{W}{2L} \mu_{eff} C_G \left[(V_{GS} - V_T)^2 - (V_{GD} - V_T)^2 \right] \quad (1)$$

$$\bar{Q}_G \approx \frac{\mu_{eff} W^2 C_G^2}{I_D} \int_0^{V_{DS}} [V_G - V_T - V]^2 dV \quad (2)$$

$$\bar{Q}_G \approx \frac{2}{3} W L C_G \left[\frac{(V_{GD} - V_T)^3 - (V_{GS} - V_T)^3}{(V_{GD} - V_T)^2 - (V_{GS} - V_T)^2} \right]$$

above threshold (linear)

$$C_{GS} = \frac{\partial \bar{Q}_G}{\partial V_{GS}} \approx \frac{2}{3} WLC_G \left[1 - \frac{(V_{GD} - V_T)^2}{(V_{GD} + V_{GS} - 2V_T)^2} \right]$$

$$C_{GD} = \frac{\partial \bar{Q}_G}{\partial V_{GD}} \approx \frac{2}{3} WLC_G \left[1 - \frac{(V_{GS} - V_T)^2}{(V_{GD} + V_{GS} - 2V_T)^2} \right]$$

$$C_{GB} = \frac{\partial \bar{Q}_G}{\partial V_{GB}} \approx 0$$

$$V_D, V_S \approx 0$$

$$C_{GS} = C_{GD} \approx WLC_G / 2$$

above threshold (saturation)

$$V_{GD} = V_{GS} - V_{DS} \quad V_{DSAT} = V_{GS} - V_T$$

$$C_{GS} = \frac{\partial \bar{Q}_G}{\partial V_{GS}} \approx \frac{2}{3} WLC_G$$

‘Meyer model’

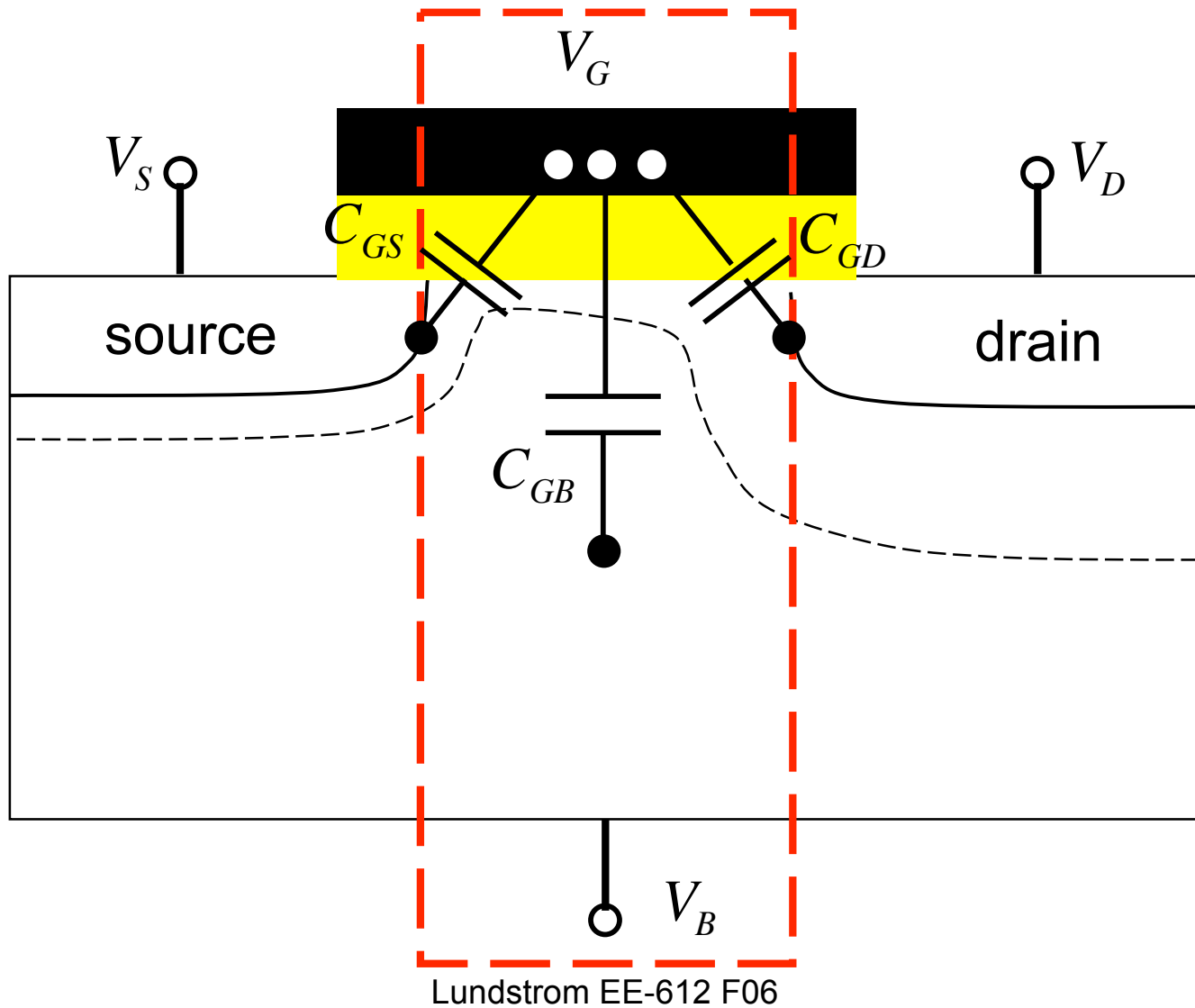
see:

$$C_{GD} = \frac{\partial \bar{Q}_G}{\partial V_{GS}} \approx 0$$

$$C_{GB} = \frac{\partial \bar{Q}_G}{\partial V_{GB}} \approx 0$$

*MOSFET Models for VLSI
Circuit Simulation*, N. Arora,
Springer-Verlag, 1993

intrinsic MOSFET C's



about MOSFET capacitances

- 1) charge conservation problems

$$Q = \int_{t_1}^{t_2} i dt = \int_{V_1}^{V_2} C(V) dV = \bar{C} [V(t_2) - V(t_1)]$$

- 2) 'charge based models'

- 3) capacitance matrix

$$i_j = \frac{dQ_j}{dt} = \frac{\partial Q_j}{\partial V_G} \frac{\partial V_G}{\partial t} + \frac{\partial Q_j}{\partial V_S} \frac{\partial V_S}{\partial t} + \frac{\partial Q_j}{\partial V_D} \frac{\partial V_D}{\partial t} + \frac{\partial Q_j}{\partial V_B} \frac{\partial V_B}{\partial t}$$

- 4) non-reciprocal capacitances

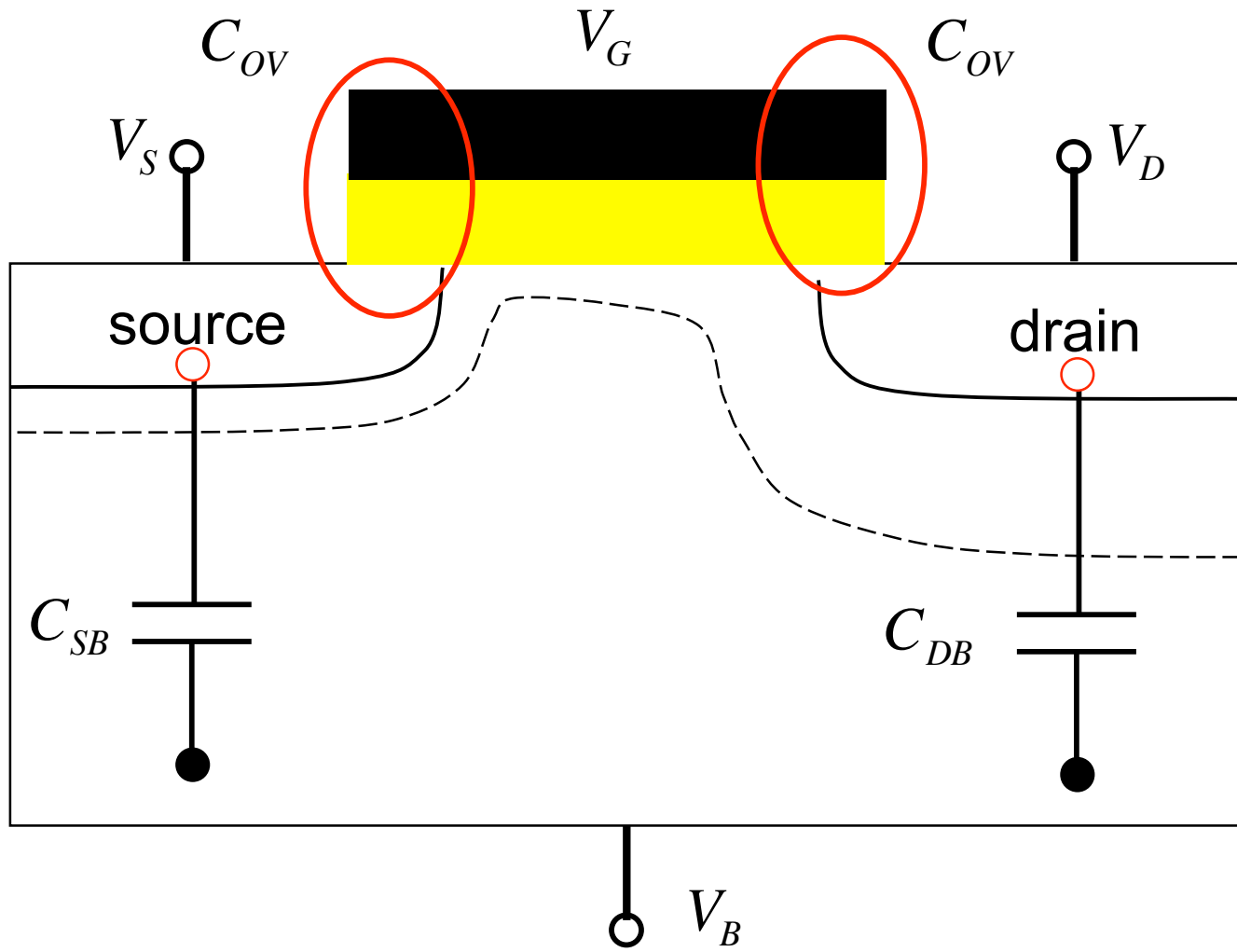
- 5) short channel effects

- 6) non-quasi-static effects

more information on capacitances

MOSFET Models for VLSI Circuit Simulation,
Narain Arora, Springer-Verlag, 1993

extrinsic MOSFET C's



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